

# IEEE SW Test Workshop

Semiconductor Wafer Test Workshop



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## Benefits of Flip Chip Wafer Sort using MEMs Multi Site Capability

Lessons learnt



GLOBALFOUNDRIES



FORMFACTOR

June 6 to 9, 2010

San Diego, CA, USA

# Outline

- **The Growing SOC Market**
- **Test Vehicle and Test Parameters**
  - Chuck Force Comparison
  - Probe Mark Comparison
- **Cleaning Considerations**
- **Yield Comparison**
- **Electrical Properties Comparison**
- **Test Performance**
- **Summary**



# GLOBALFOUNDRIES – Who Are We?

## Global Manufacturing Operations



### Fab 8

Future leading-edge  
300mm manufacturing  
Saratoga County, NY



### Fab 2, 3, 3e, 5, 6

Mainstream 200mm manufacturing  
campus  
Woodlands, Singapore  
Tampines, Singapore



### Fab 1

Leading-edge 300mm  
manufacturing campus  
Dresden, Germany



### Fab 7

Mainstream 300mm  
manufacturing campus  
Woodlands, Singapore

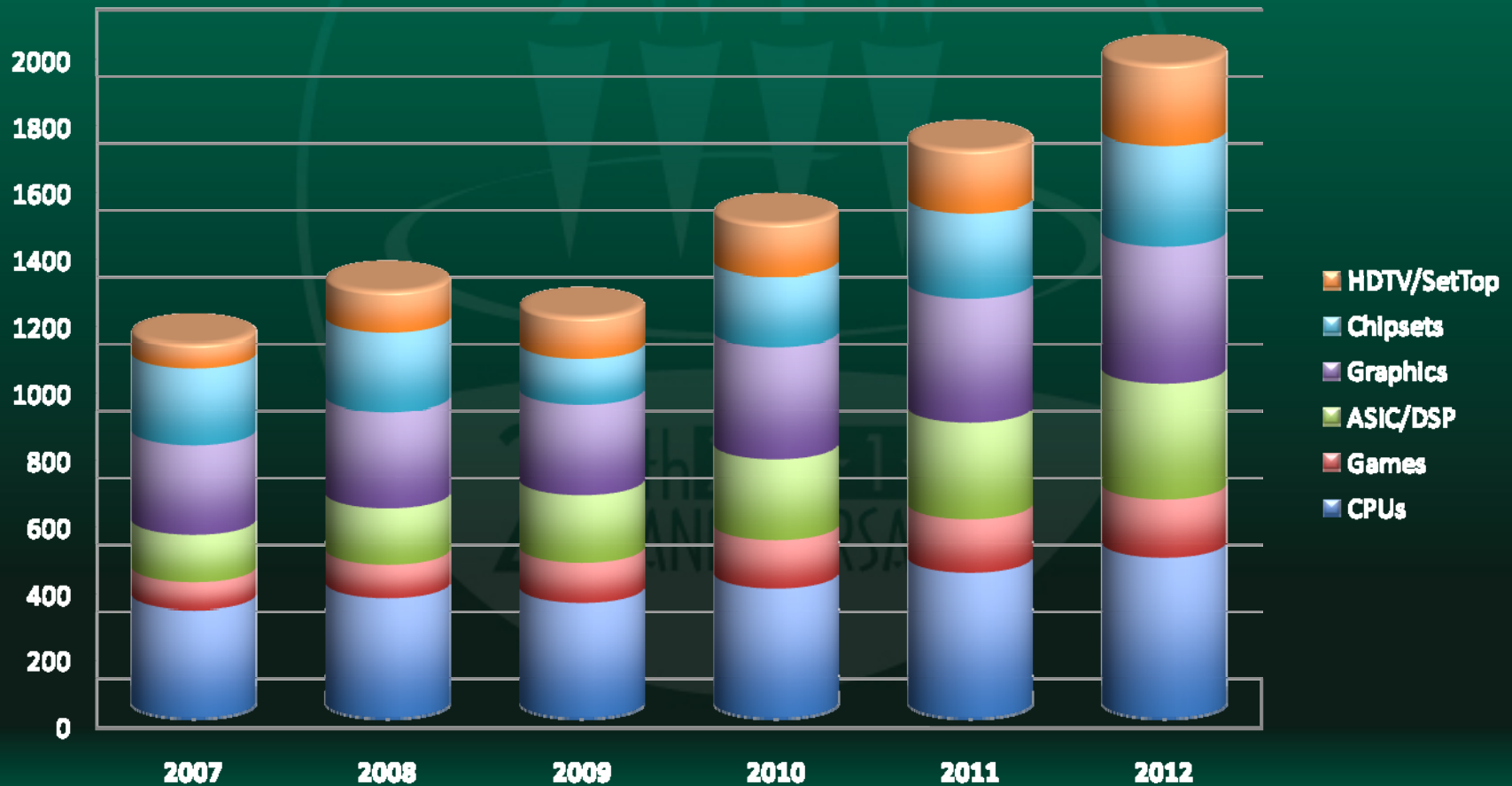


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# Motivation for Vertical / MEMs Technology

## Flip Chip Market Trend



Source : TechSearch International Inc.

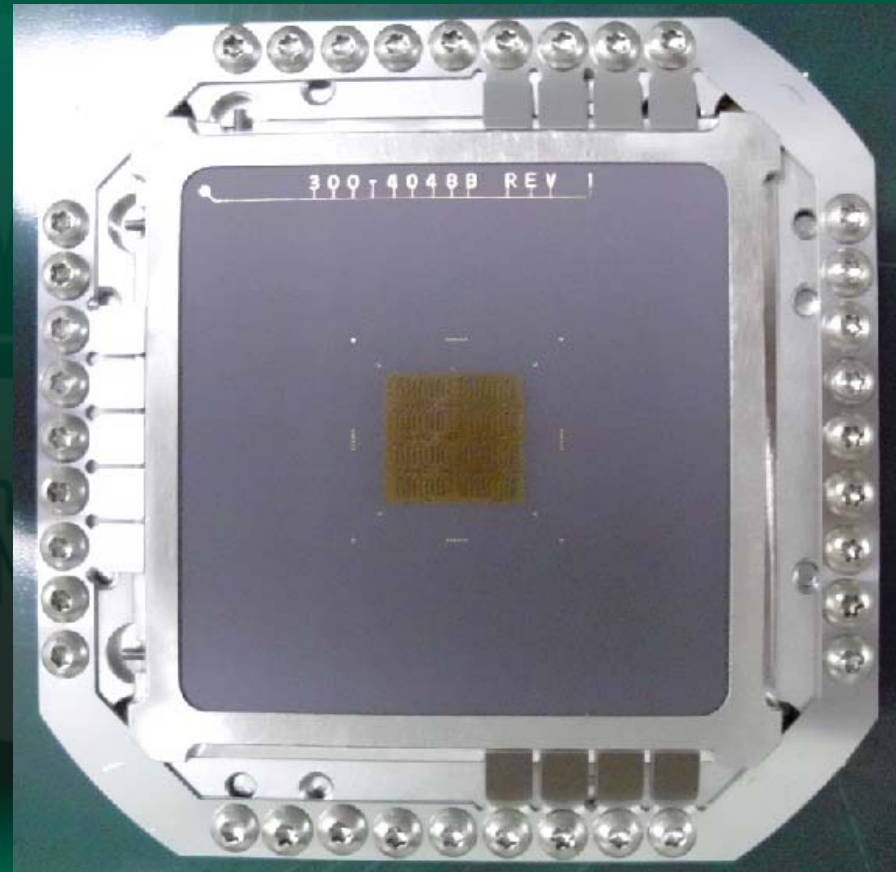
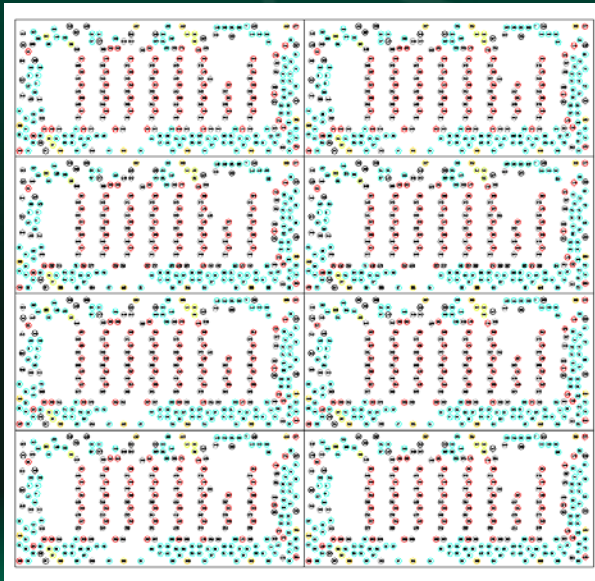


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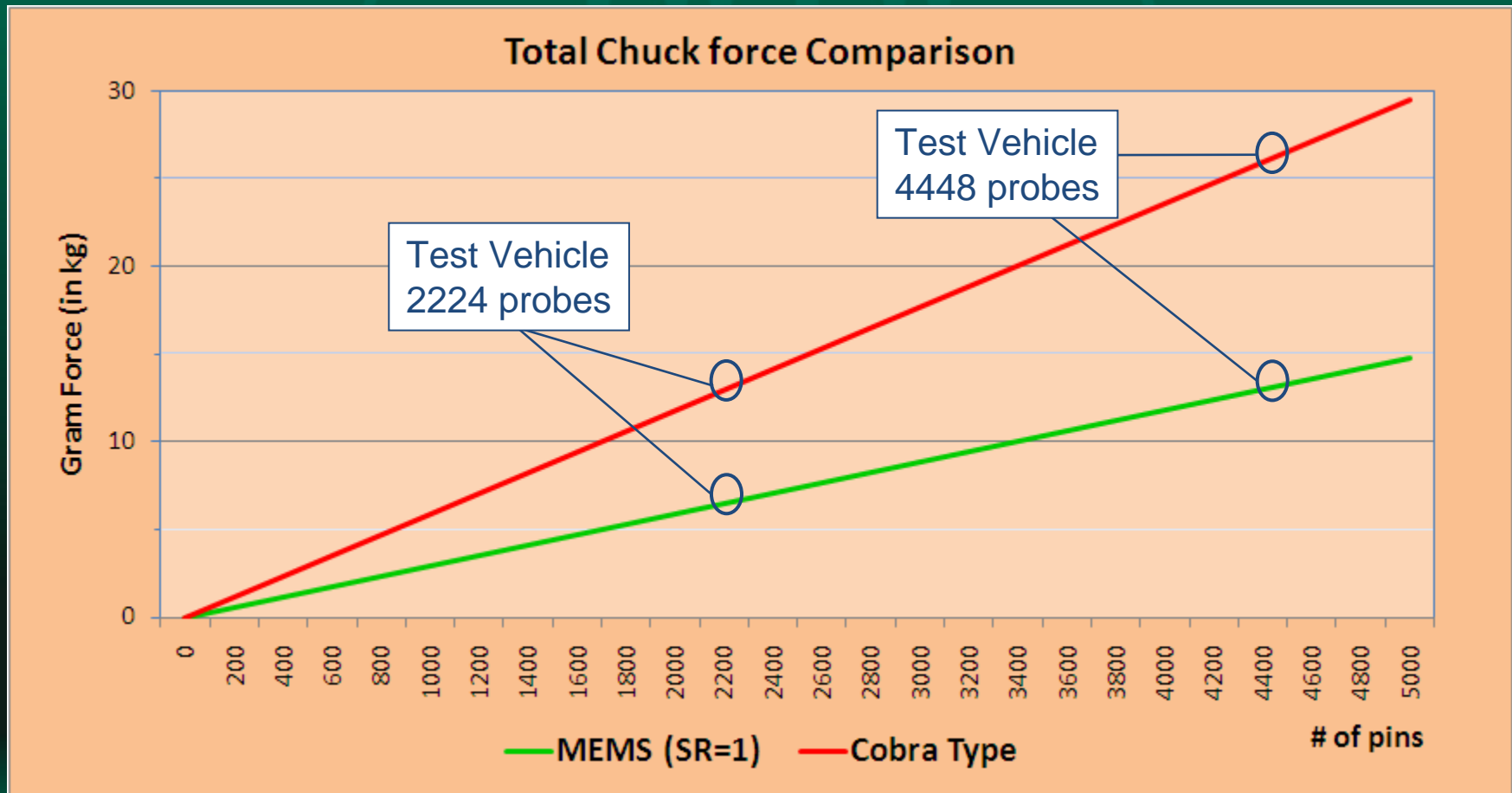
# Test Vehicle Information

- **Application: Universal Mobile Telecommunication Chip**
- **Technology Node: 65nm**
- **Die Size: 3.4mm x 7.1mm**
- **Pitch: 180um**
- **Bump Material: Eutectic**
- **Probe Count per Die: 278**
- **Multi-Site: 2 x 4 Solid Array**



# Probe-card Chuck Force Comparison

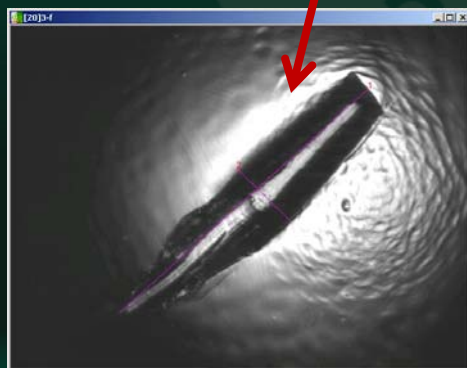
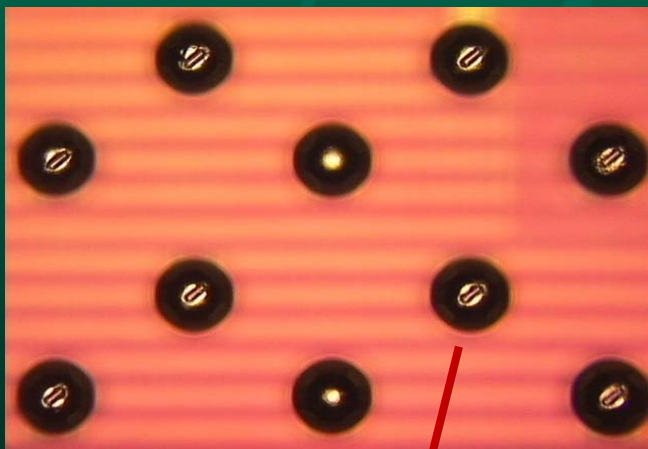
- Significant increase in chuck force needed for Vertical probe with higher pin count



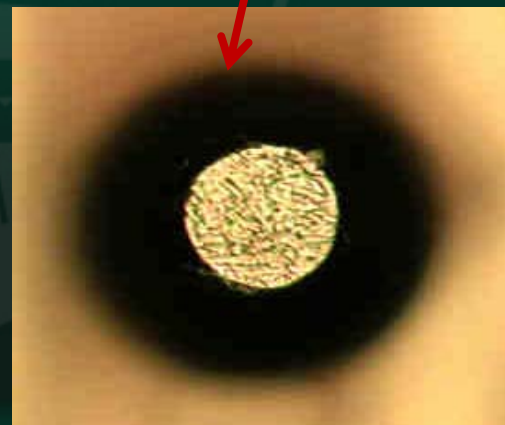
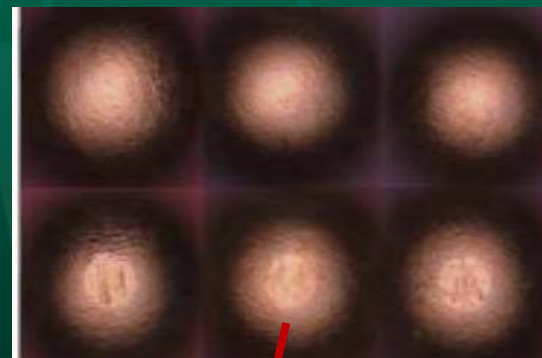
# Probe Mark Comparison (MEMS vs Vertical)

- Characteristics of the probe marks

MEMS probe marks

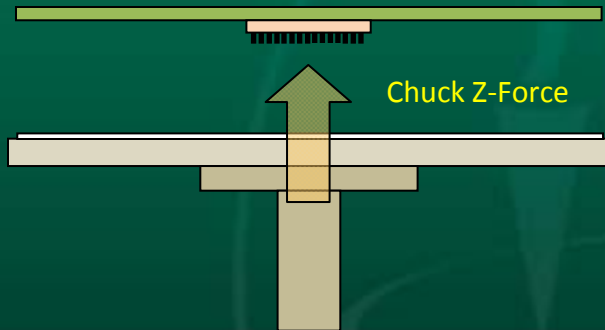


Vertical probe marks



# Impact of Higher Chuck Force on Higher Parallelism

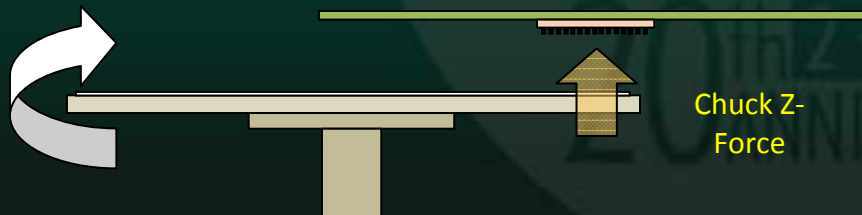
Pressure of probe head at center of check



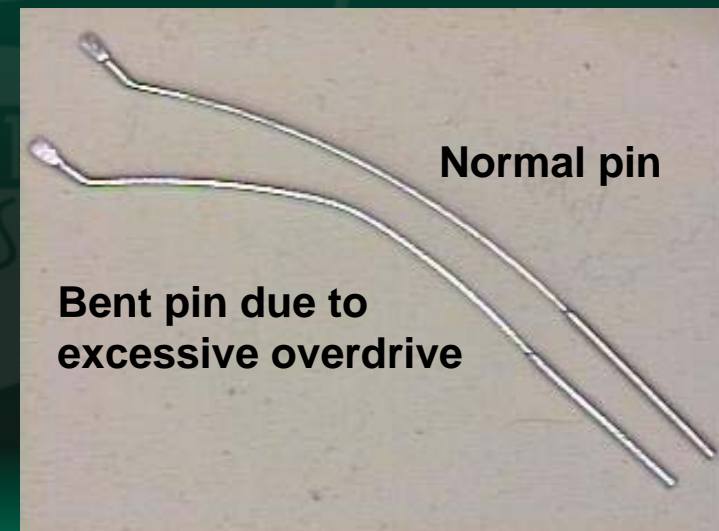
Improper overdrive with excessive chuck force



Pressure of probe head at edge of check



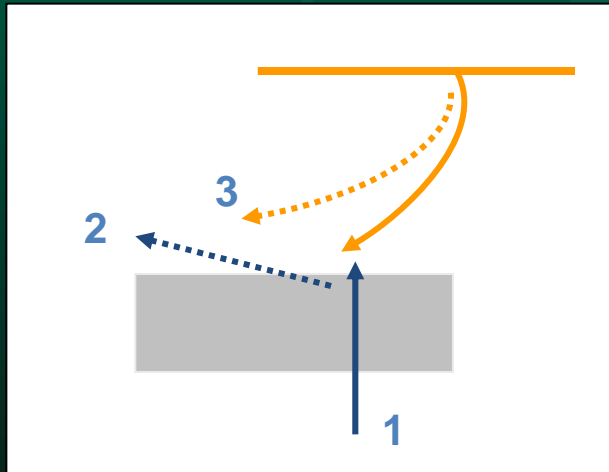
Note : Need to change to a stronger chuck



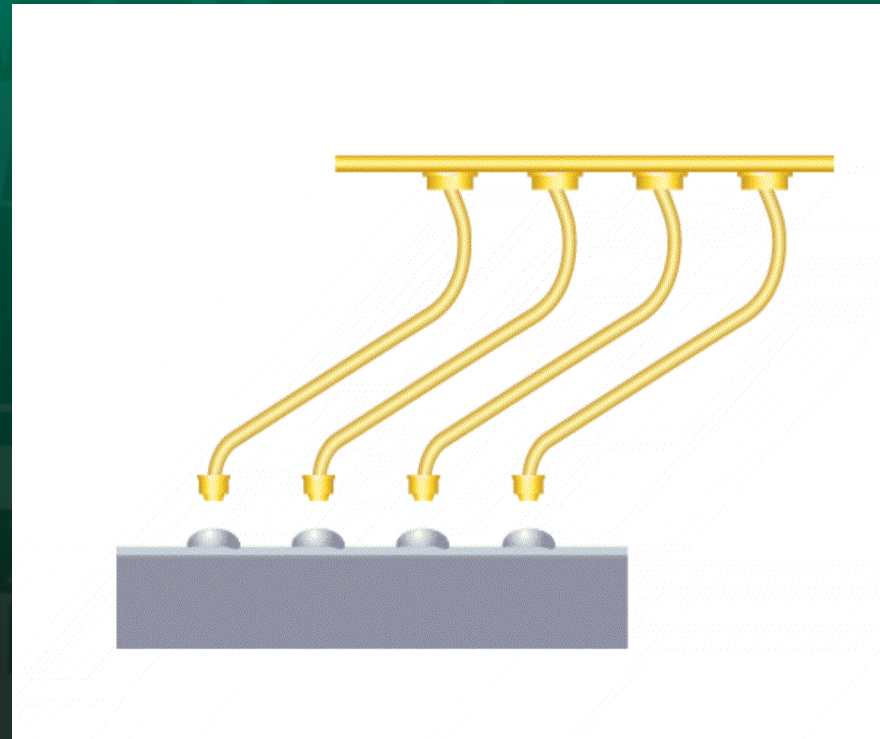


# Overcoming the Impact : MicroForce™ Probing

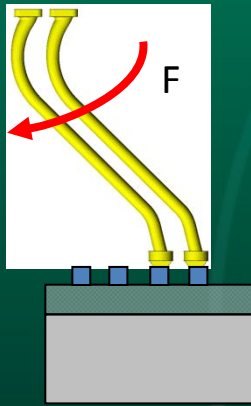
- What is MicroForce™ probing?
  - It is a coordinated X-Y-Z probing motion



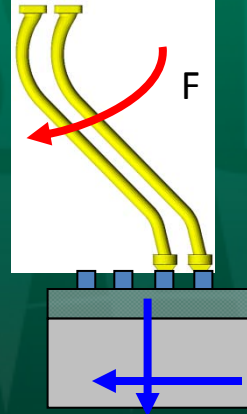
- 1 – Prober Chuck Moves in Z-axis
- 2 – Contact with Flip Chip Bump
- 3 – Chuck moves in X-Y-Z



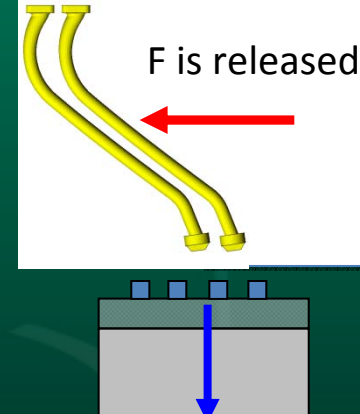
# Improvements on MEMS PC : Enhanced Self-Cleaning MicroForce™ Recipe



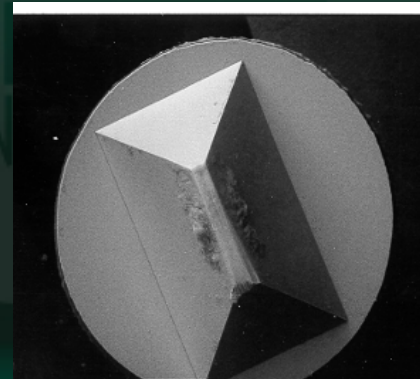
- F has been created during the XYZ Up motion



- Start XYZ Down motion
- Self Cleaning Phase 1

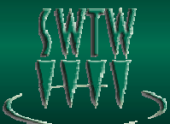


- Start Z only Down motion
- Self Cleaning Phase 2



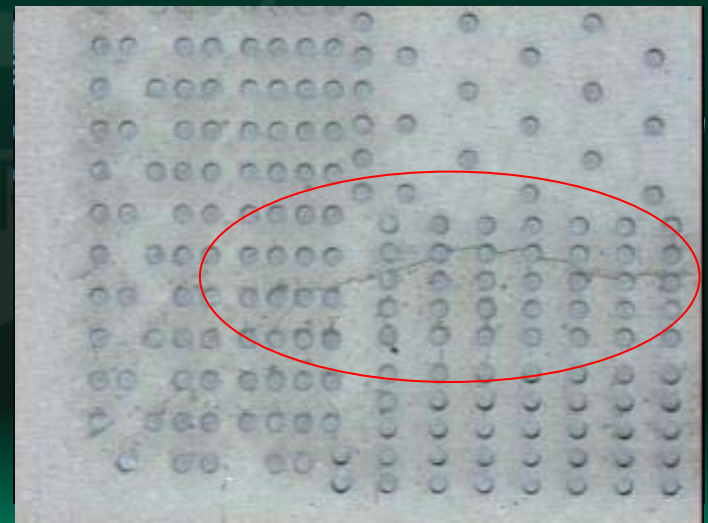
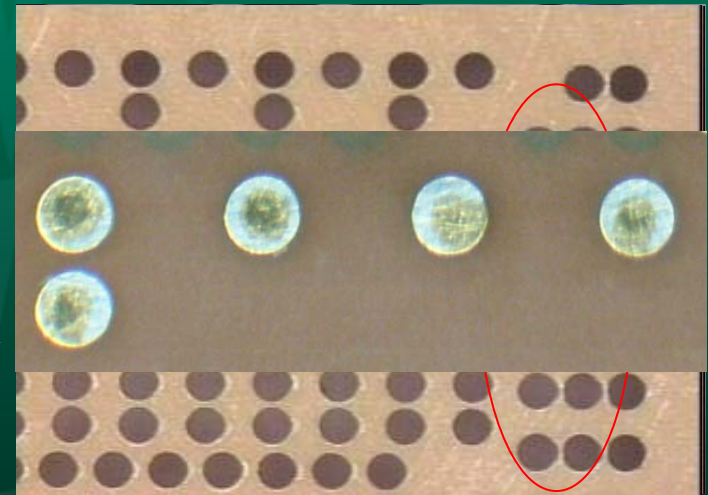
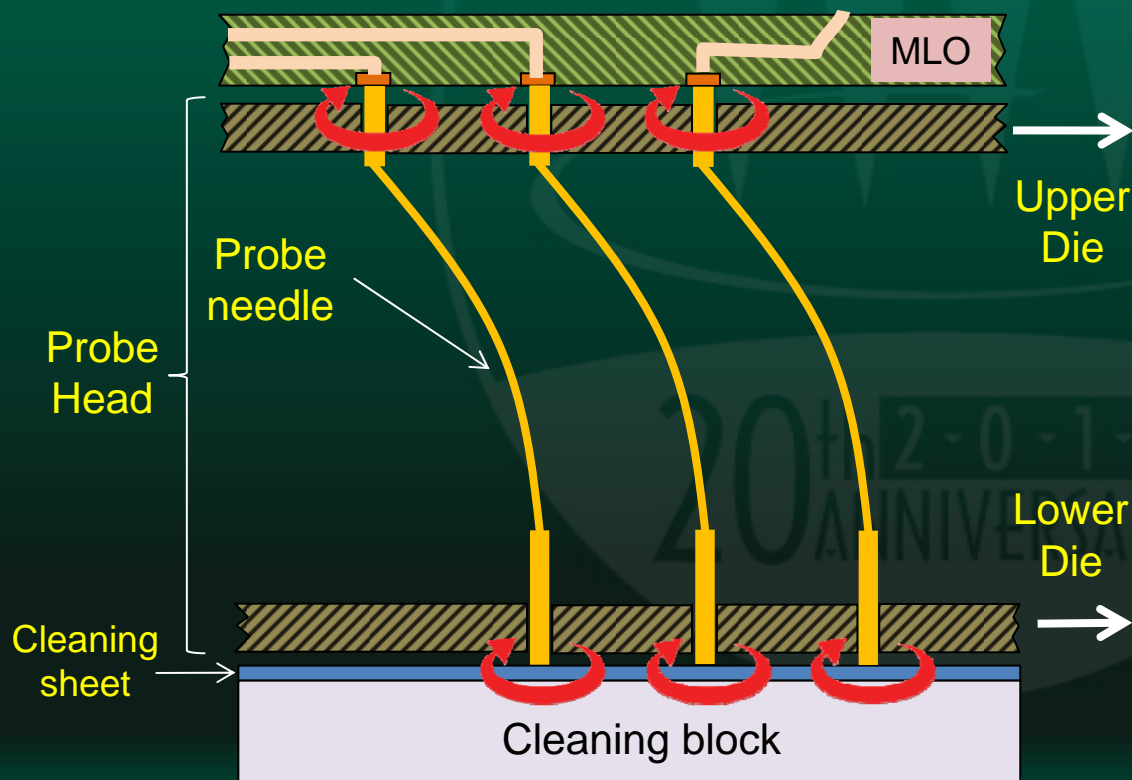
Impact:  
With self cleaning option, online cleaning frequency lowered by 16X!!

Results : Self Cleaning Effect



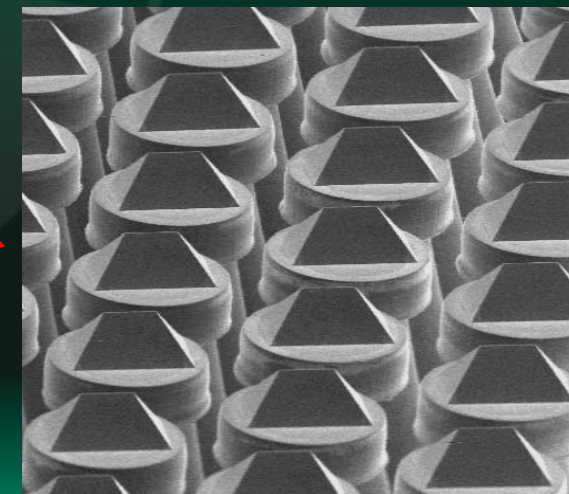
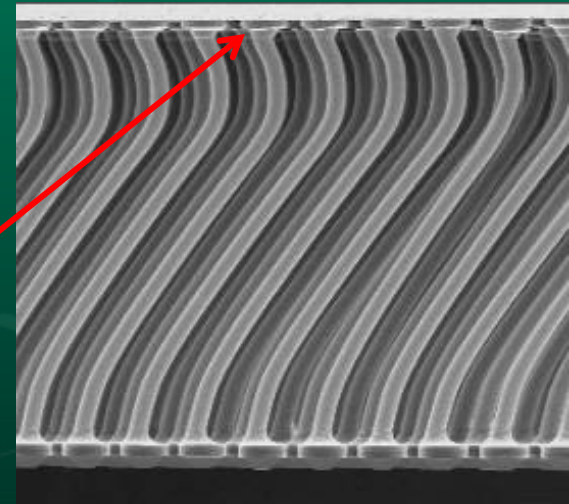
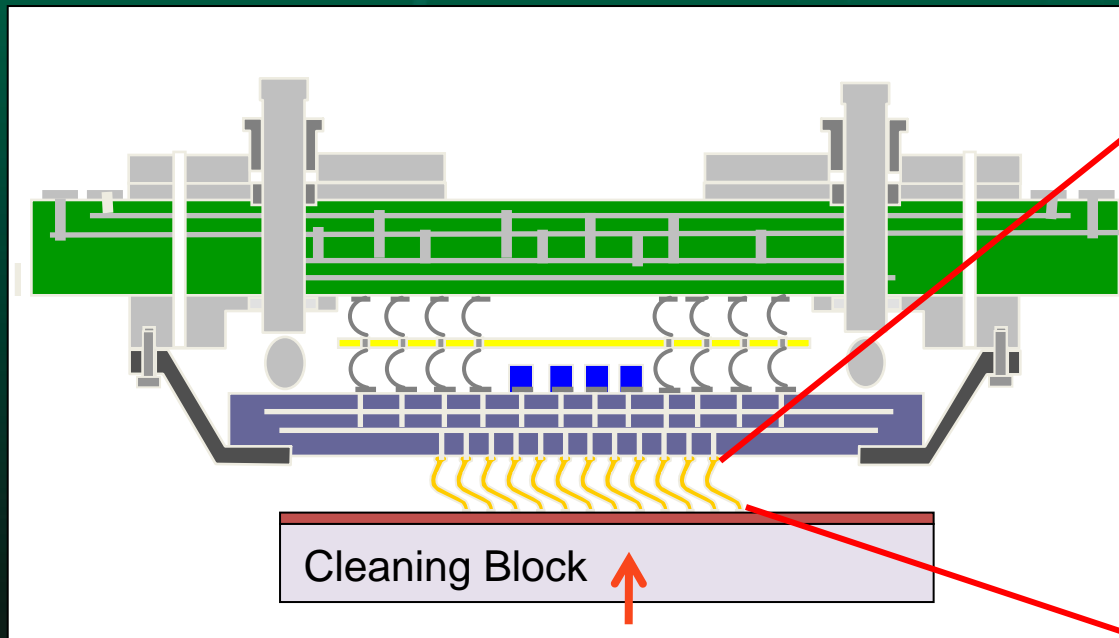
# Impact of High Chuck Force on Online Cleaning (Vertical)

- Vertical Probe Head Construct



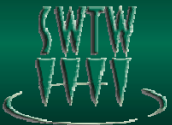
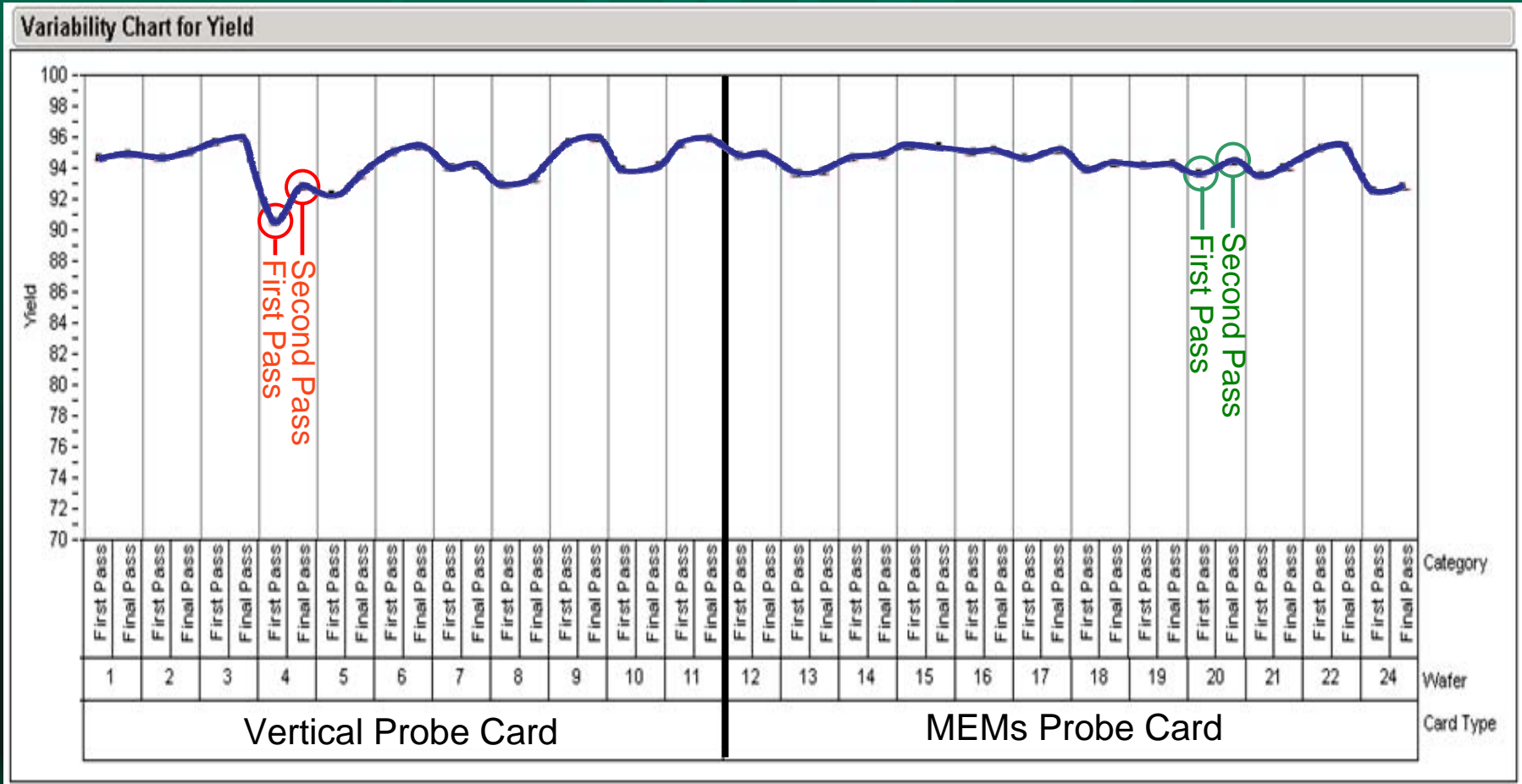
# Impact of High Chuck Force on Online Cleaning

- MEMS Probe Head Construct



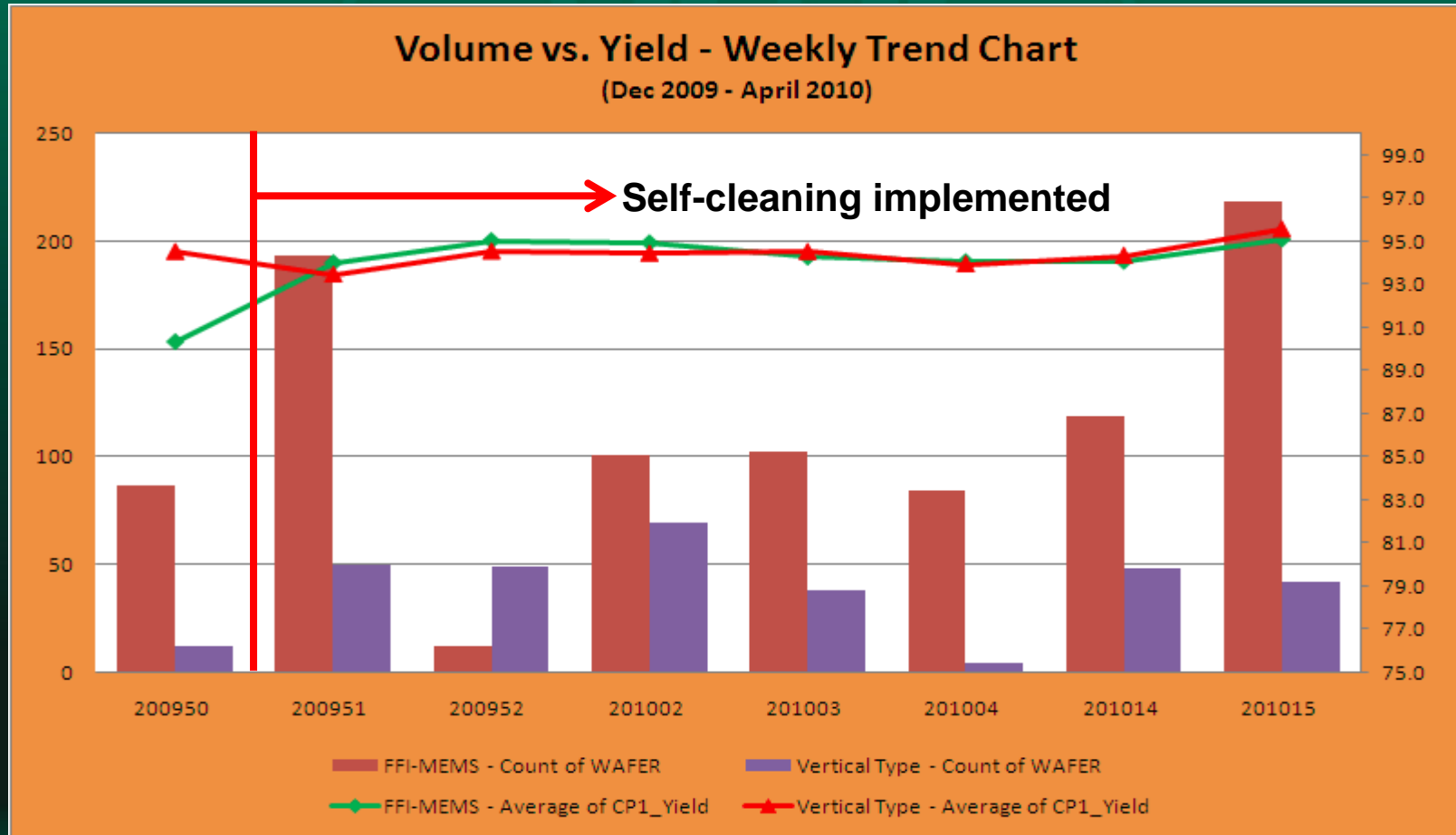
# MEMs vs Vertical Probe Cards

- Yield Comparison



# Impact of Self Cleaning : Yield

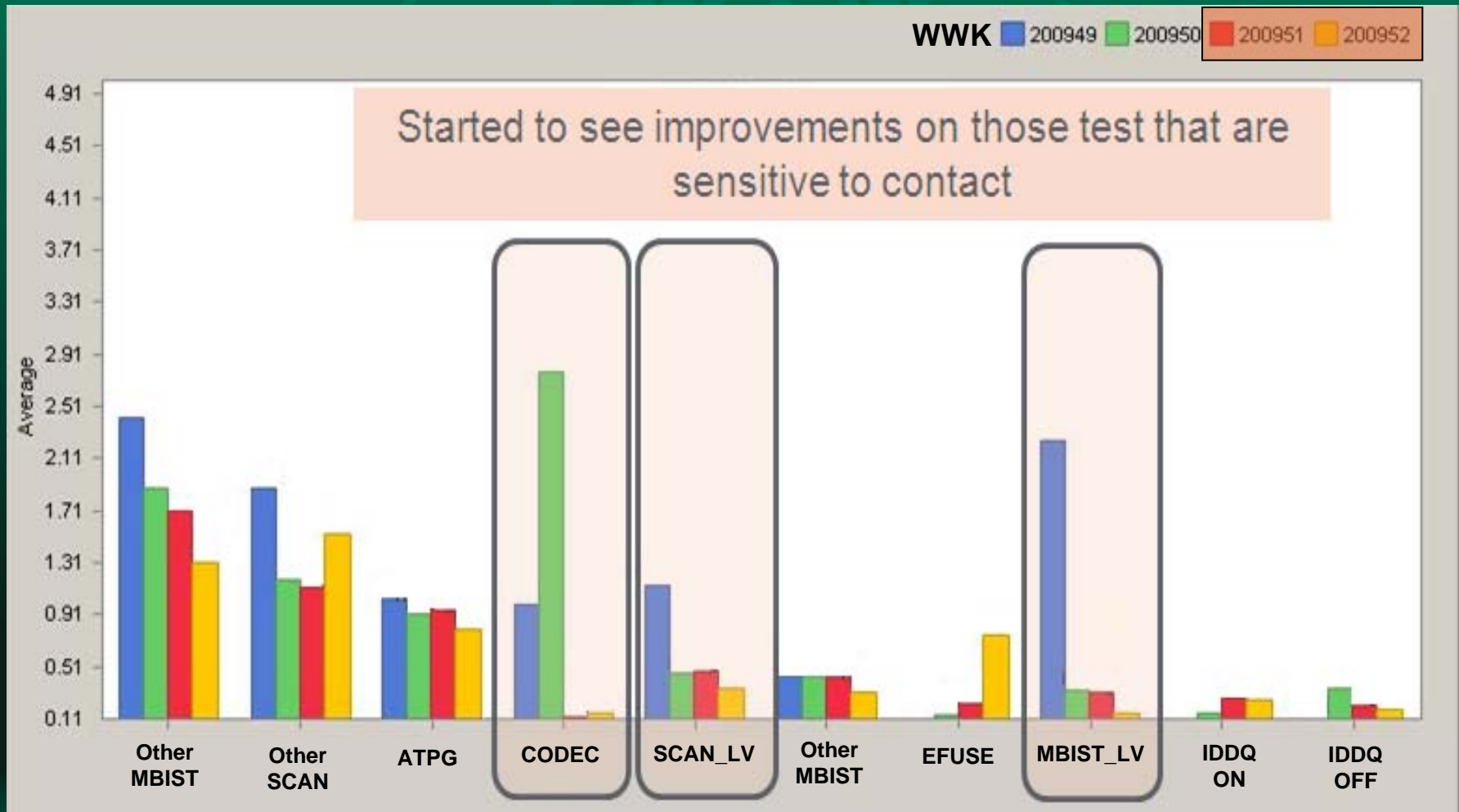
- Significant improvement in yield after implementing self-cleaning



# Impact of Self Cleaning : Contact Sensitive Failures

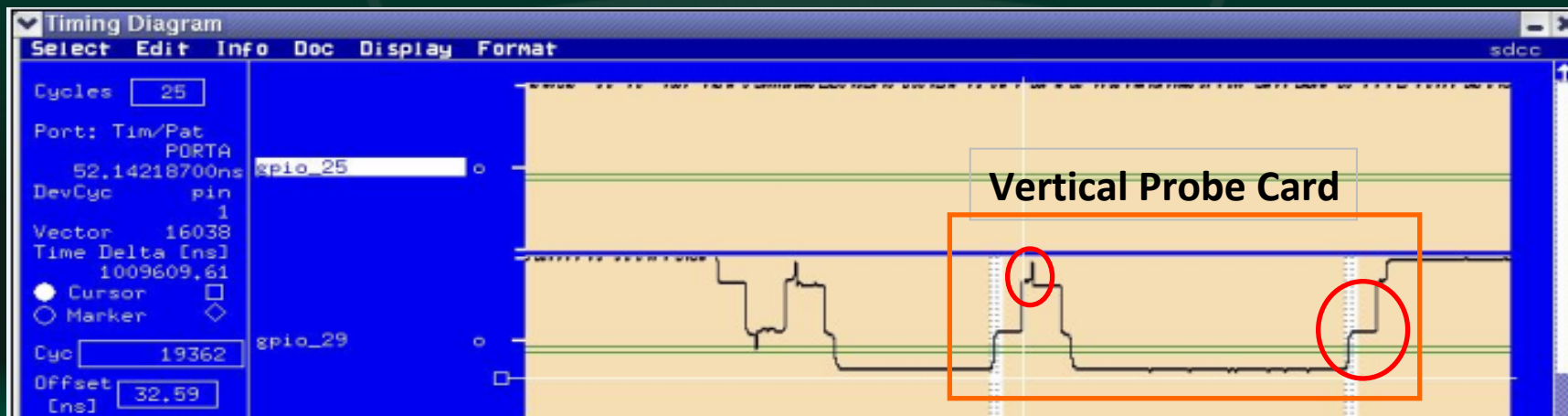
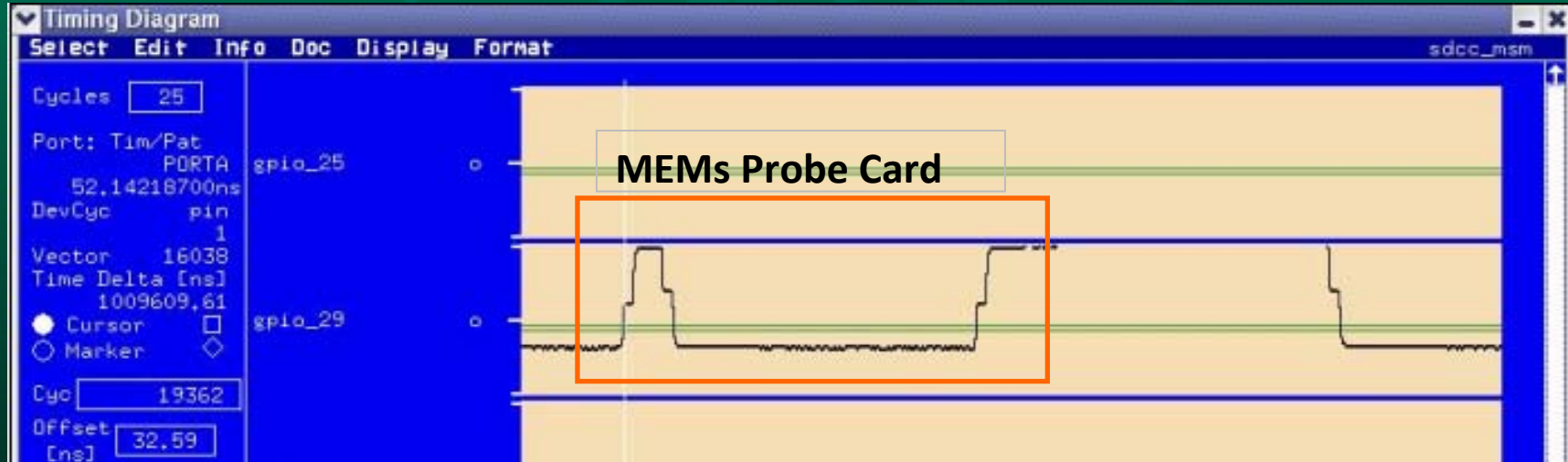
- Reduction in contact related failures

Implementation of self-cleaning



# Electrical Properties Comparison

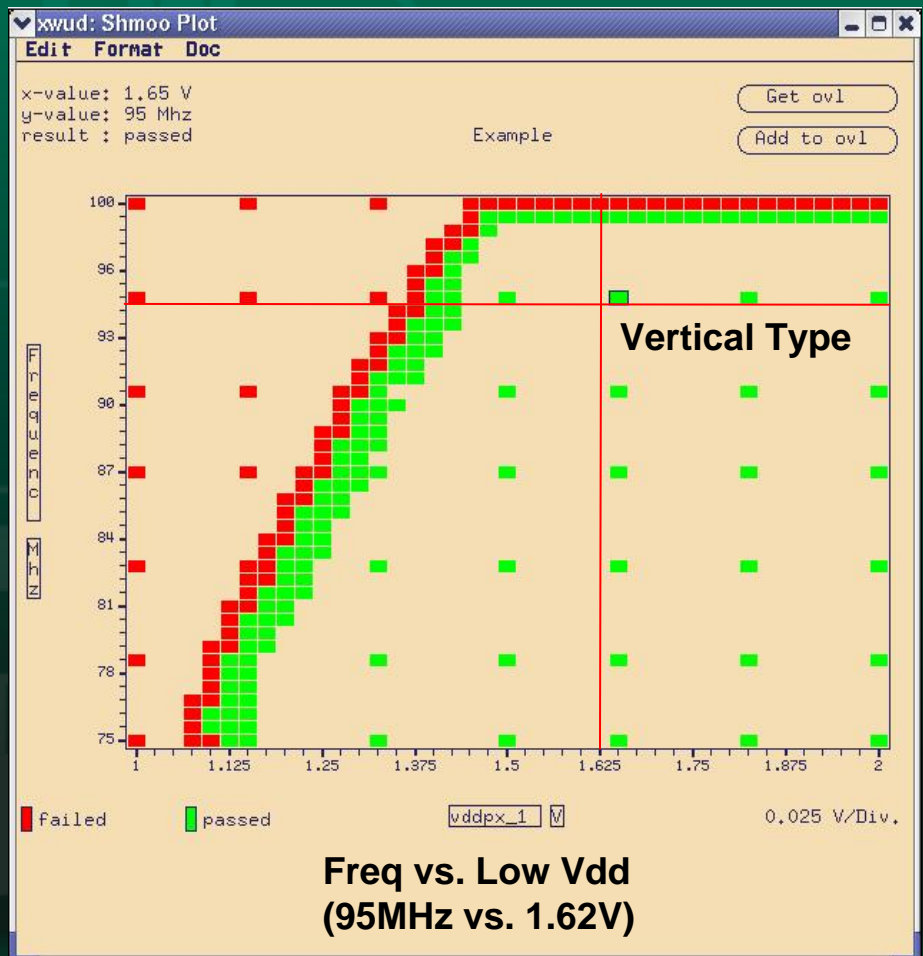
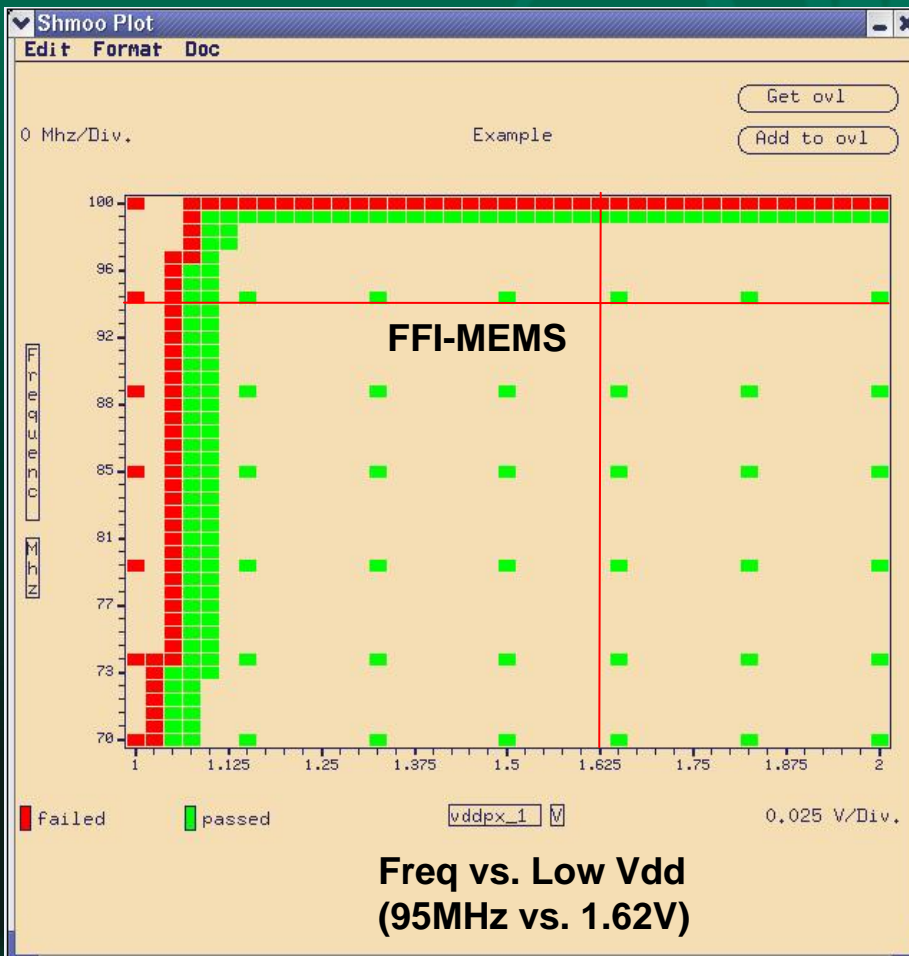
- Experienced timing delay for some functional test block (~15ns)





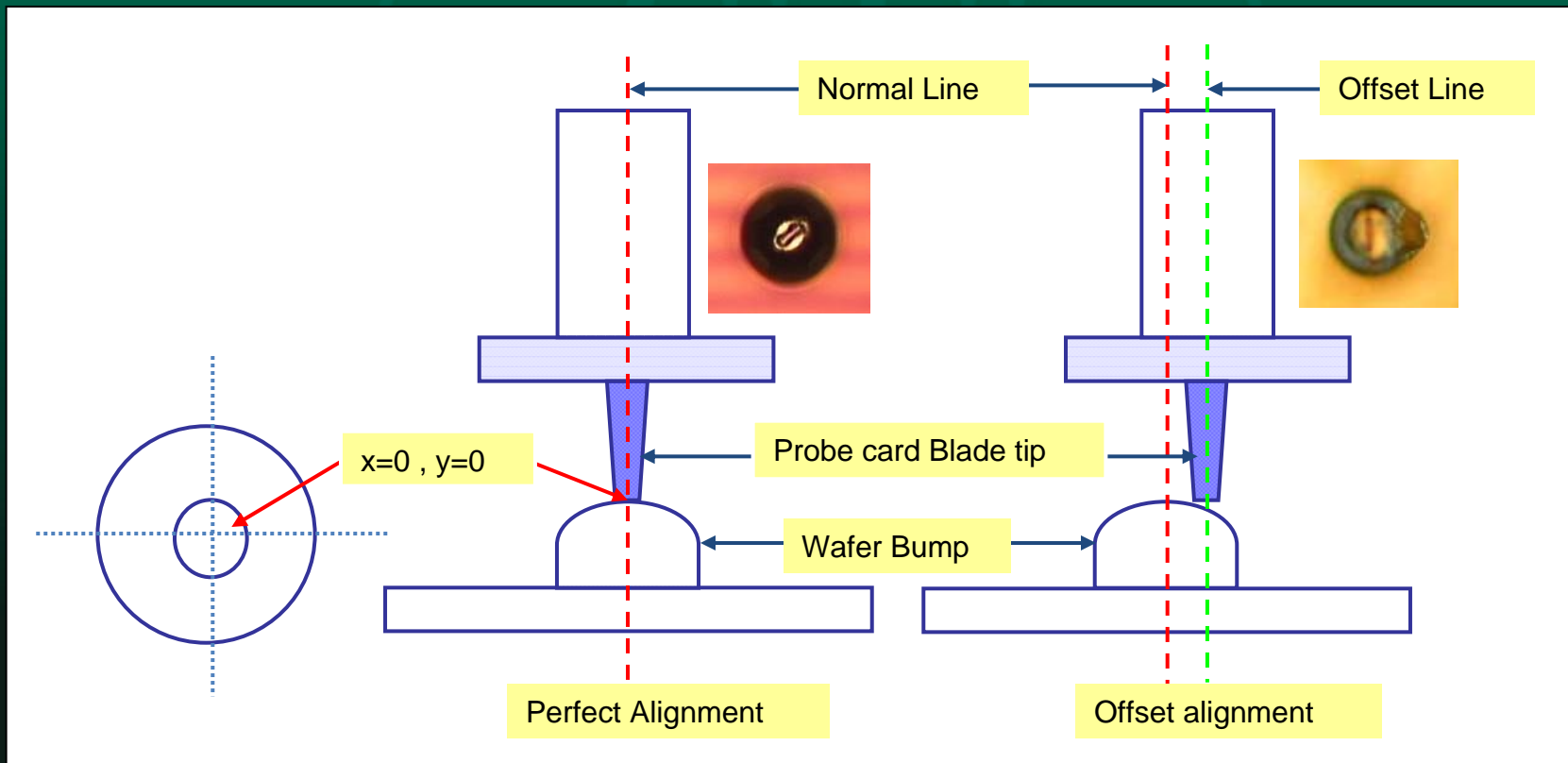
# Test Performance Comparison

- Experienced better margin in some functional test block



# MEMS PC : Caveats

- A tool is only as good as the skills of the user
  - Improper setup leading to quality issue



# Summary

## ■ Positive learning

- Better Yield stability over time
- Better Electrical performances
- Lower down time with implementation of online self-cleaning
- Experienced lower Z-force with MicroForce™ (ease into higher parallelism)
- MEMs architecture allows easy migration to higher multi sites test
- Presence of probe mark to help with the setup and troubleshooting
- No MLC damage with MEMs technology

## ■ Caveats

- Need to ensure Microforce™ option is installed on prober prior to using.
- Susceptible to probe mark issue if not setup properly
- Limited pin replacement capability



# Acknowledgements

## GLOBALFOUNDRIES:

Bernardo Montemayor, Jeffrey Lam, Yeo Chak Huat

## FormFactor:

Xin Ying Ng, John Kao, Kevin Chung, Robert Murphy, ChanPin Chong

## ASET:

Chris Bunao, Jeofill Caballero, MJ Kuo

## Amkor:

Orange Ou, Yeong Sun Lee

## SCT:

Alli Su, Cass Chen, Chao Liang, Colin Chen

## Semics:

Ralph Yang, Kai Yoon, Paul Shin



THANK YOU

# Q & A

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